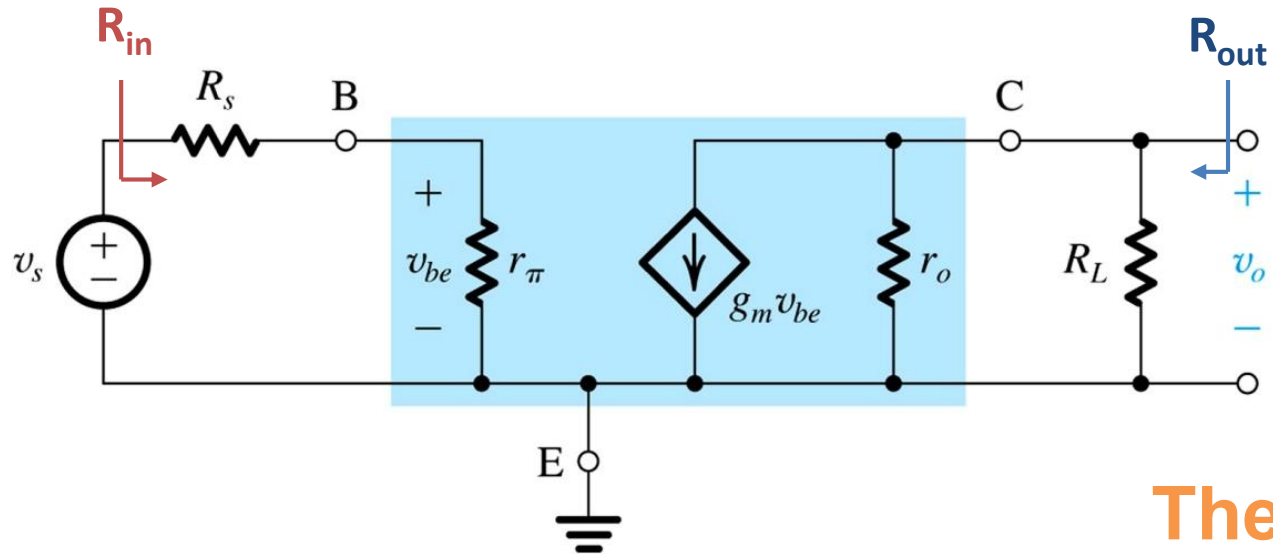


Last Lecture → Input / Output Resistance

8/19/2019



R_{in} → input impedance

R_{out} → output impedance

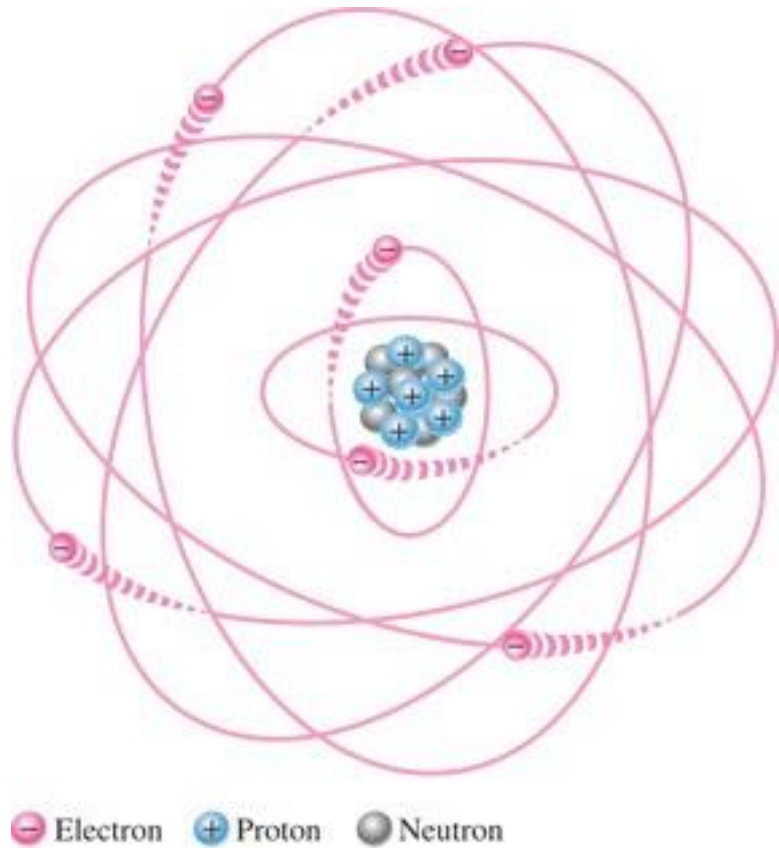
Thevenin's Resistance

- No dependent Source
 R_{th} → series / parallel combination
- Dependent Source
Place test source $V_x=1V$ at terminals

$$R_{th} = \frac{V_x}{I_x} = \frac{1}{I_x}$$
- For R_{out} turn "off" input source!

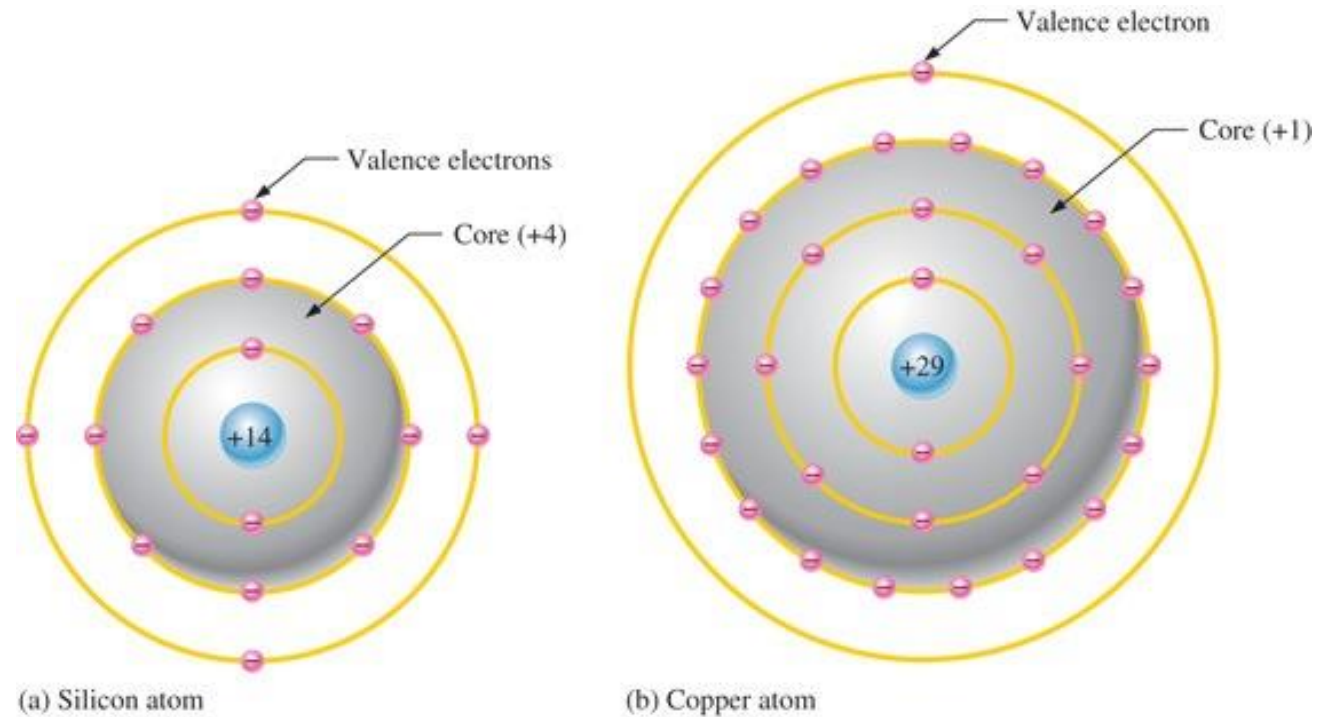
Atom – Bohr Model → Chp. #3

8/19/2019



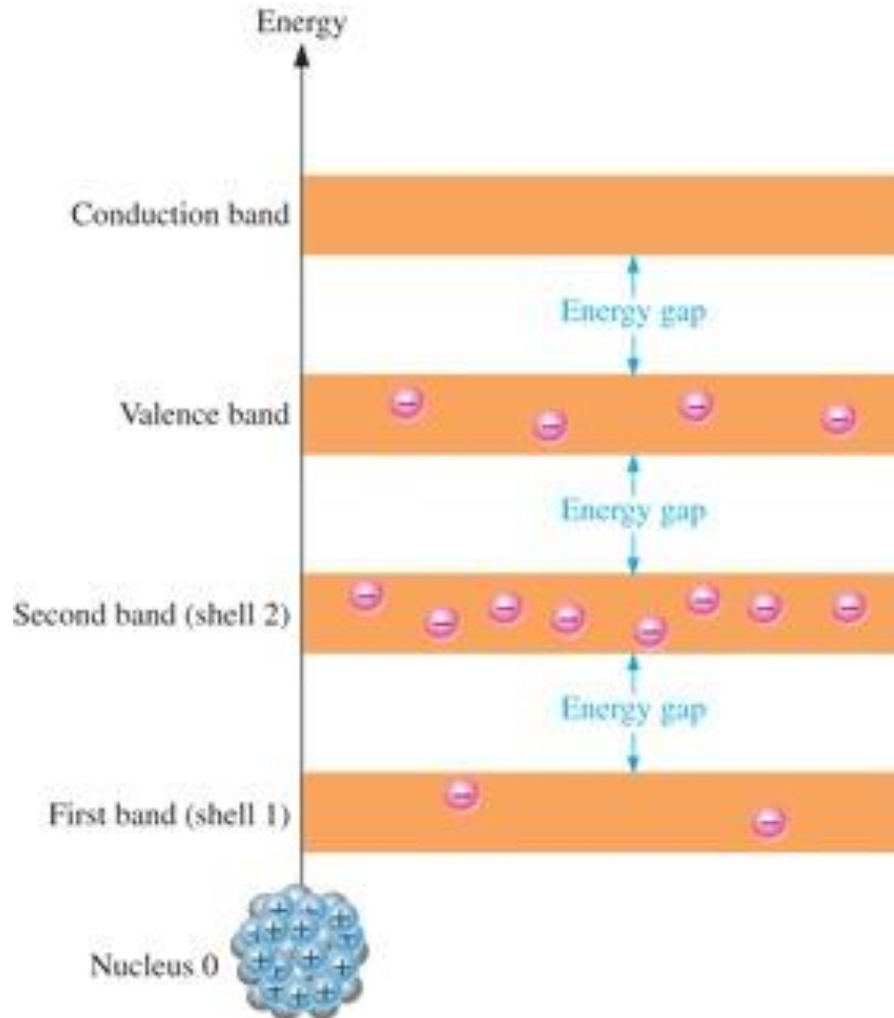
... **electrons** move in orbits around the nucleus, which consists of **protons** and **neutrons**.


- Elements in the periodic table are grouped according to the number of **valence electrons**.
- **Valence electron** – an electron that participates in the formation of **chemical bonds**.

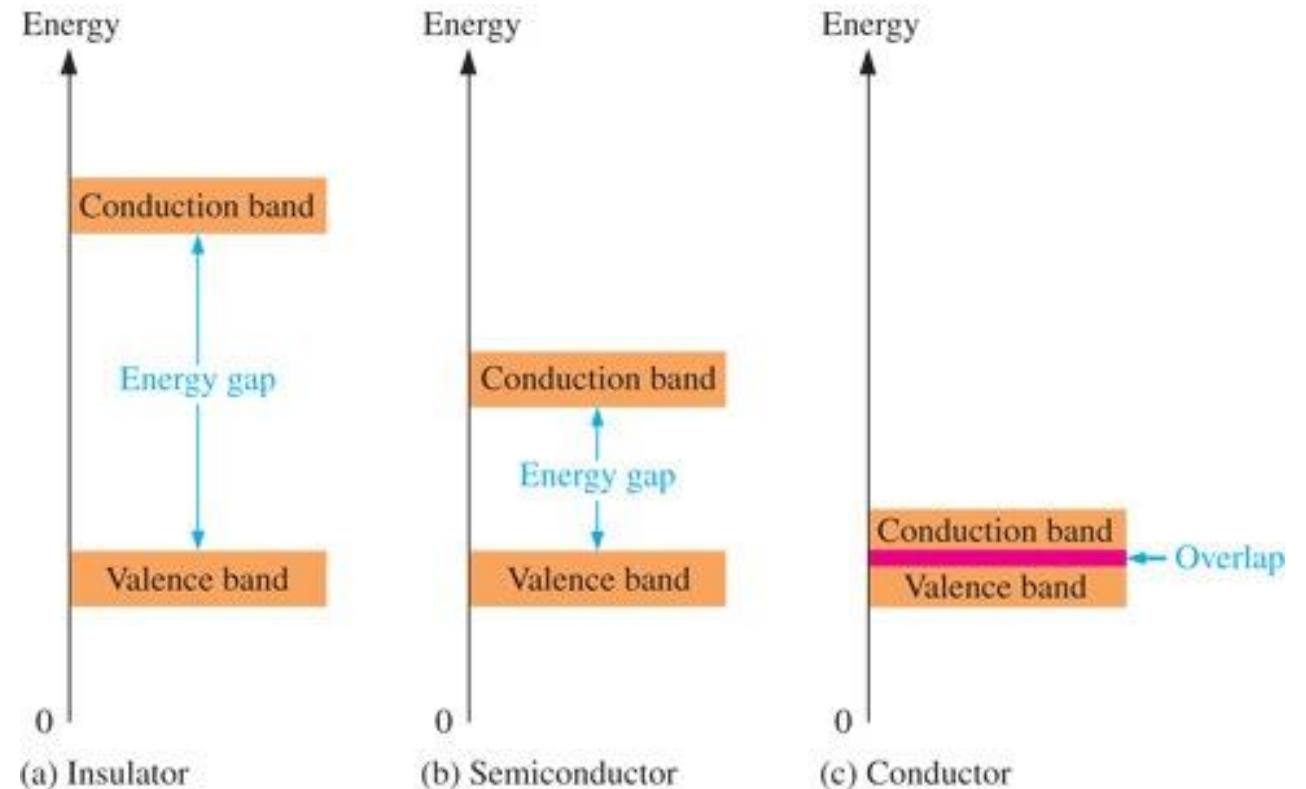


Energy Diagram

8/19/2019



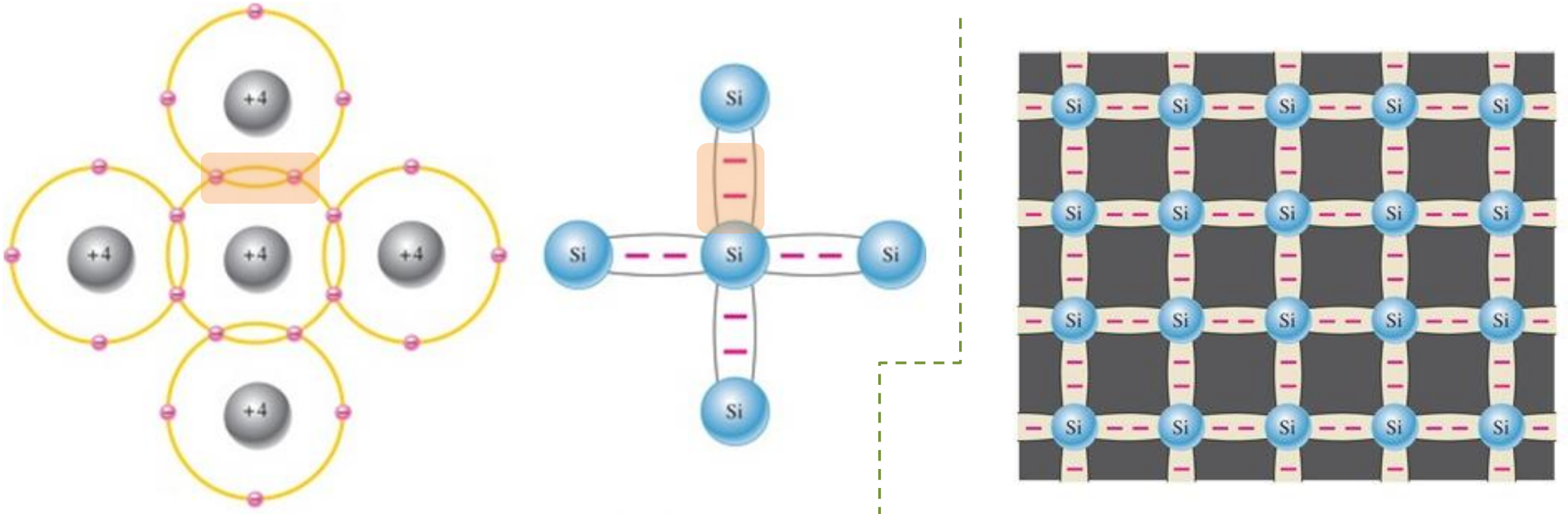
- **Energy Gap (E_g)** – minimum energy needed by a valence electron in order to jump into the conduction band.
- **Types of Material** 



Covalent Bonds

8/19/2019

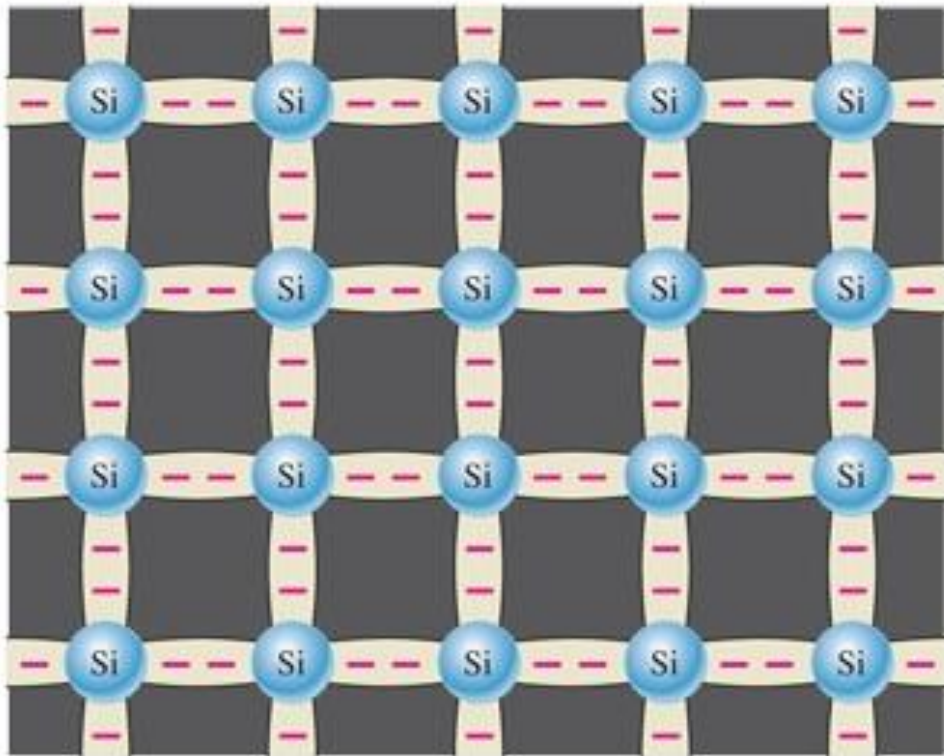
- As silicon atoms come into proximity to each other, the valence electrons interact to form a crystal
- The **valence electrons are shared between atoms**, forming what are called **covalent bonds**, a stable balance of attractive and repulsive forces between atoms.



Silicon Crystal

8/19/2019

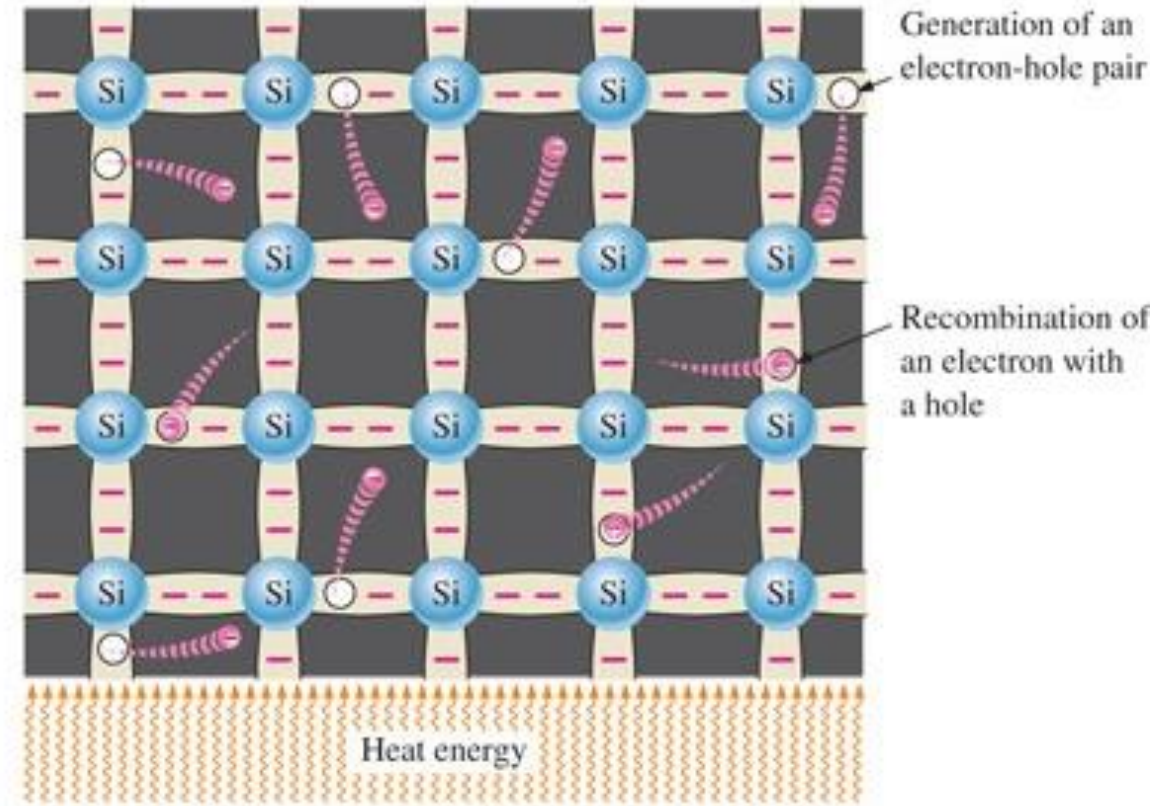
@ low temp.



- All **covalent bonds** are intact
- No **electrons** are available for conduction
- **Conductivity** is zero



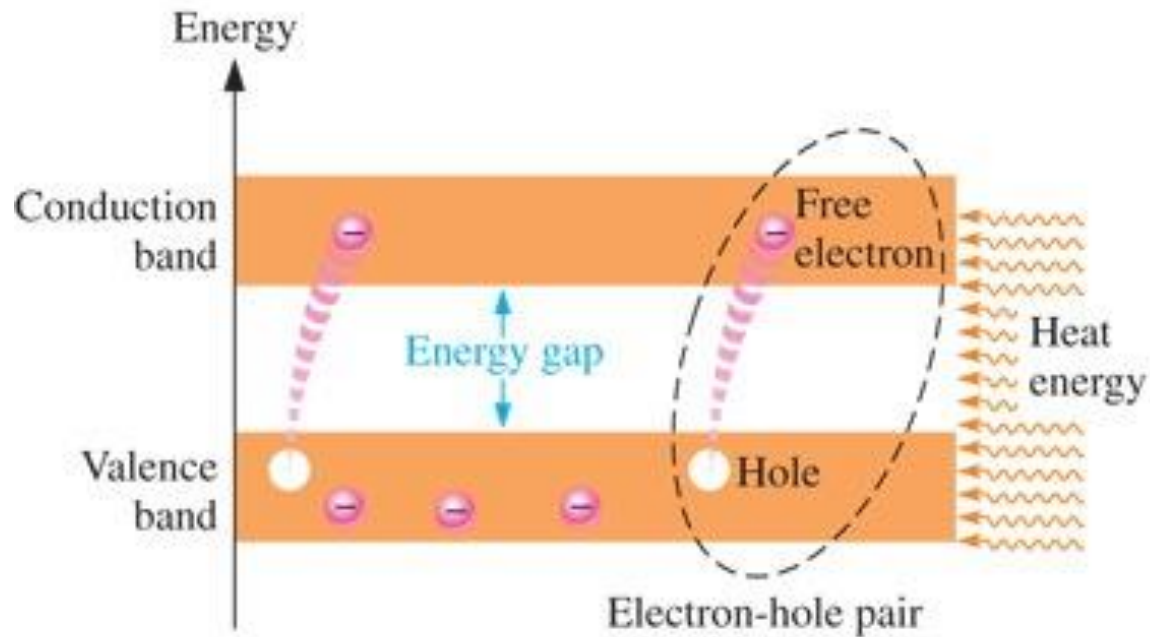
@ room temp.



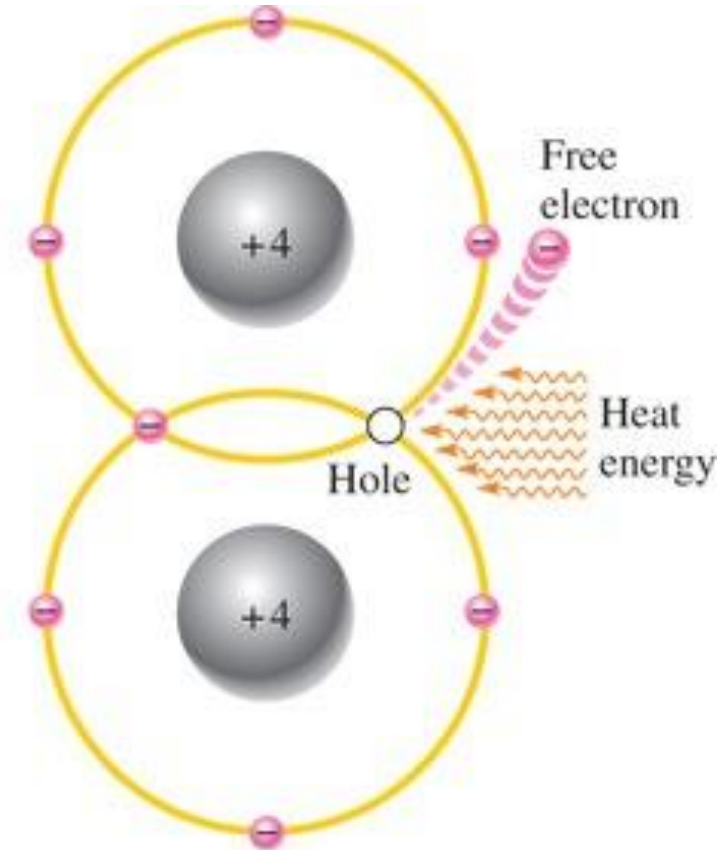
- Some **covalent bonds** break
- Some **electrons** will become available for conduction
- **Conductivity** is greater than zero

Hole – Electron Pair Creation

8/19/2019



(a) Energy diagram



(b) Bonding diagram

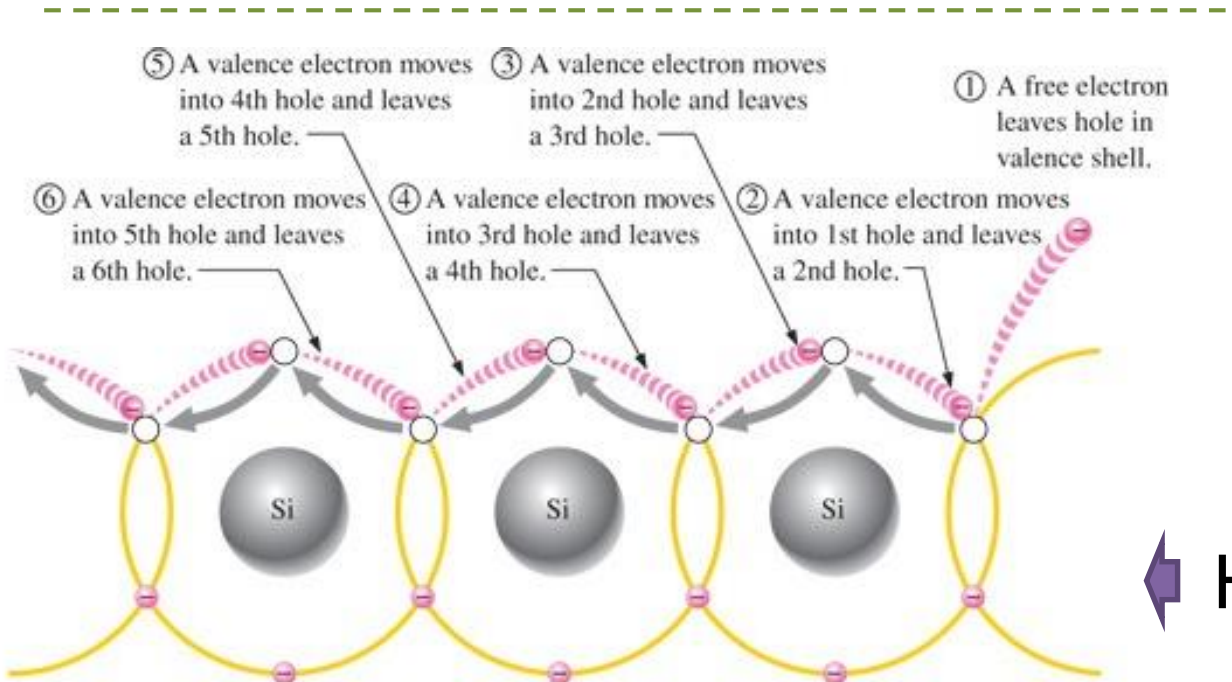
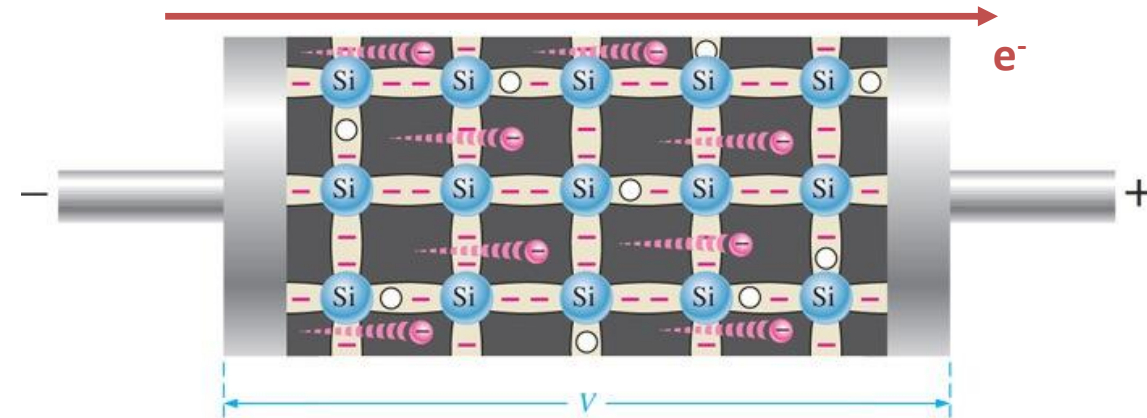
The process of freeing electrons, creating holes, and filling them **facilitates current flow...**

Electron / Hole Current

8/19/2019

Electron Current

- Movement of **free electrons** in the **conduction band**



When a valence electron moves left to right to fill a hole while leaving another hole behind, the hole has effectively moved from right to left. Gray arrows indicate effective movement of a hole.

Hole Current

- Movement of electrons in the **valence band**

Silicon Crystal → Intrinsic Charge Concentration

8/19/2019

- concentration of free electrons → n
- concentration of free holes → p

$$n = p = n_i$$



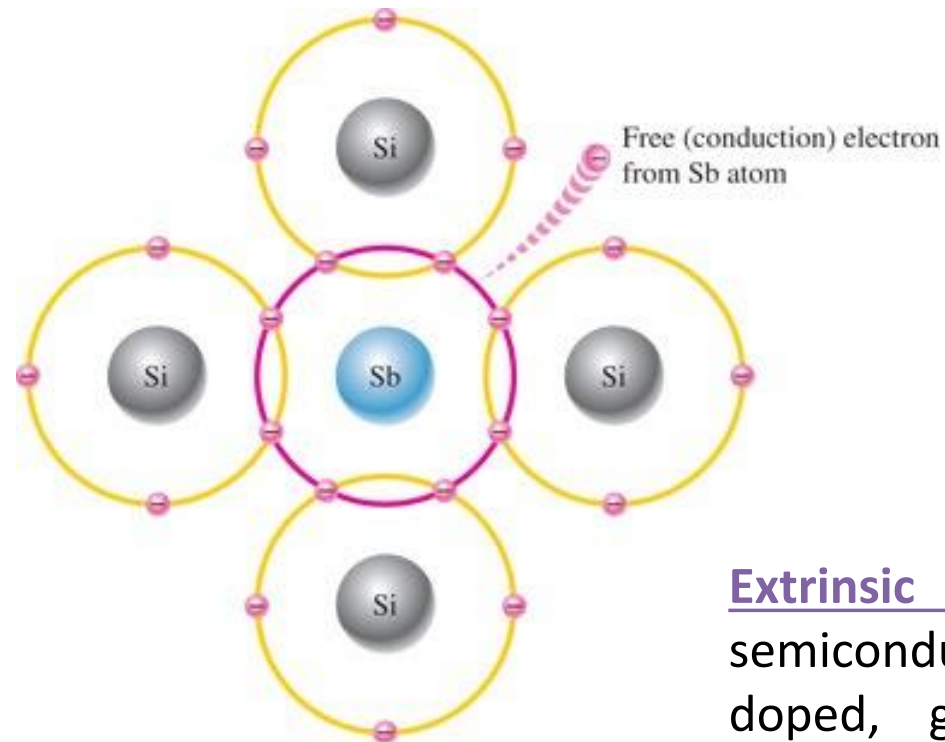
$$np = n_i^2$$

number of free electrons and holes in a unit volume (cm^3) of intrinsic silicon at a given temperature

$$n_i = BT^{3/2}e^{-E_g/2kT}$$

- material-dependent parameter → B
- bandgap energy → E_g
- Boltzmann's constant → k
- Temperature → T

Doping: addition of impurities to the intrinsic semi-conductive material. Increases the number of current carriers.

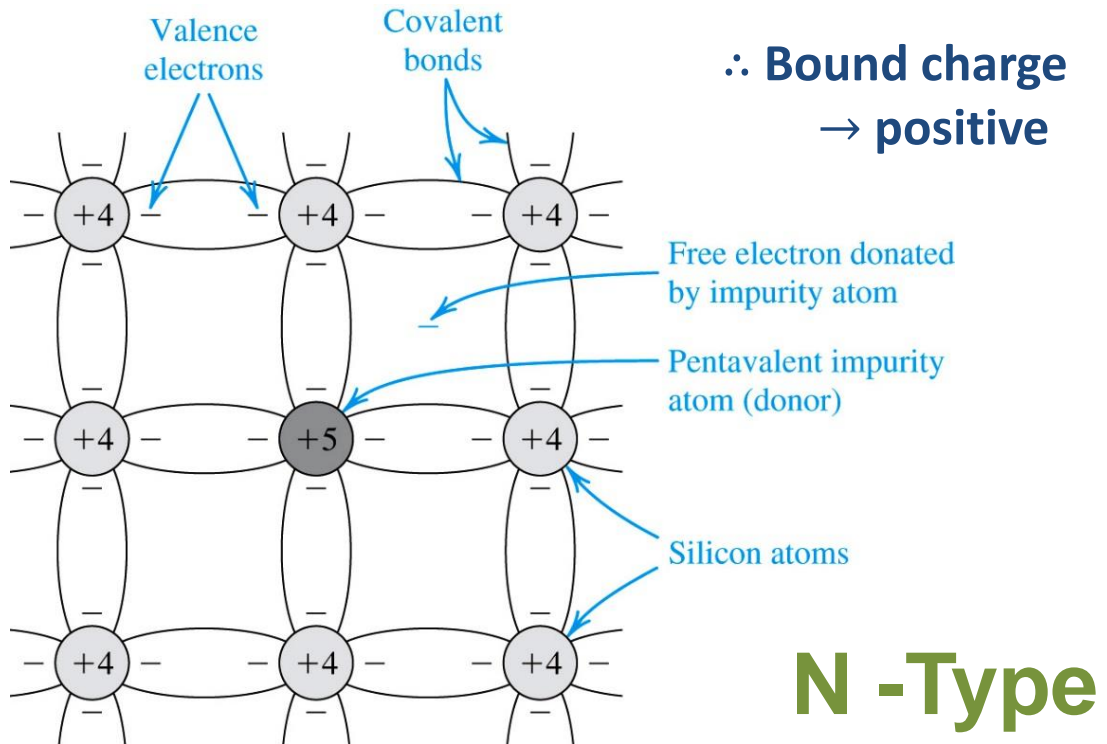


Extrinsic Semiconductor: a semiconductor that has been doped, giving it different electrical properties

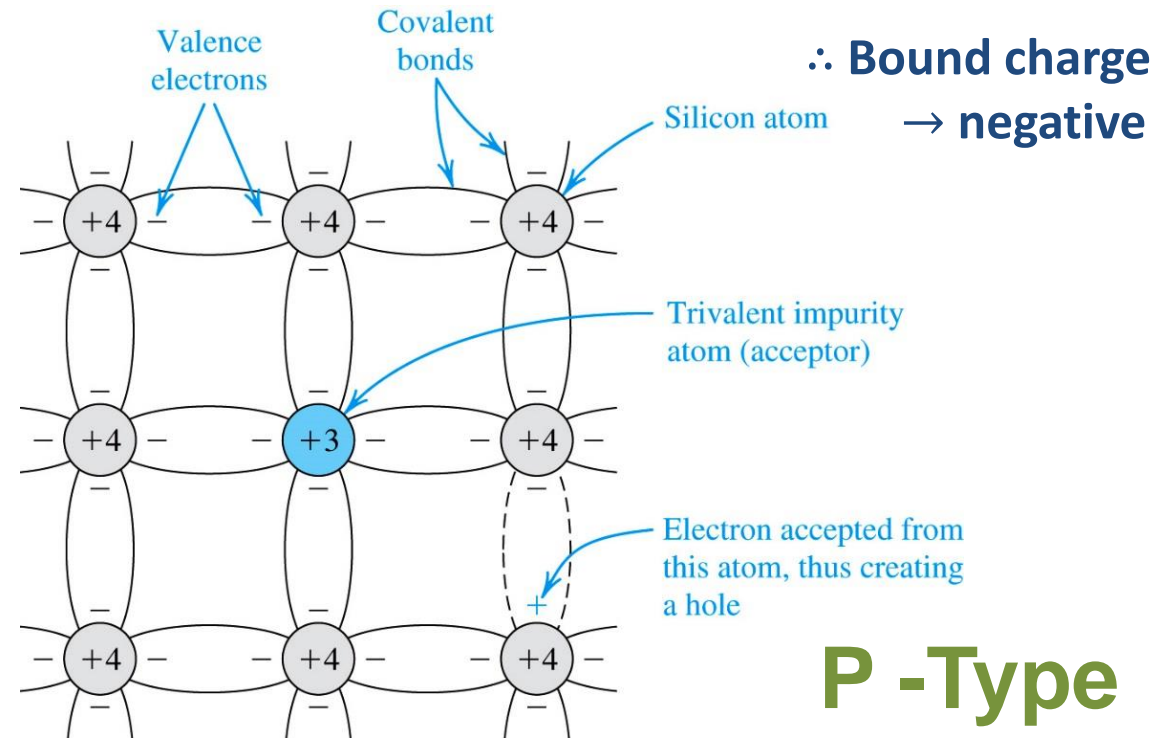
Semiconductor Types

8/19/2019

- **Antimony (Sb) – 5 Valence Electrons**
- **n-type: electrons >> holes**
 - Majority carriers – electrons
 - Minority carriers - holes



- **Boron (B) – 3 Valence Electrons**
- **p-type: holes >> electrons**
 - Majority carriers – holes
 - Minority carriers - electrons



Semiconductor Types

8/19/2019

N -Type Semiconductor

- concentration of donor atoms $\rightarrow N_D$
 - concentration of free electrons in the n-type silicon $\rightarrow n_n \simeq N_D$
- $$\therefore p_n \simeq \frac{n_i^2}{N_D}$$

P -Type Semiconductor

- concentration of acceptor atoms $\rightarrow N_A$
- concentration of holes in the p-type silicon $\rightarrow p_p \simeq N_A$

$$\therefore n_p \simeq \frac{n_i^2}{N_A}$$

A piece of n-type or p-type silicon is electrically neutral; the charge of the majority free carriers are neutralized by the bound charges associated with the impurity atoms.

Exercise 3.3:

For silicon crystal doped with boron, what must N_A be if at $T=300\text{K}$ the electron concentration drops below the intrinsic level by a factor of 10^6 ?

$$B=7.3 \times 10^{15} \text{ cm}^{-3} \text{K}^{-3/2}, \quad E_g=1.12 \text{ eV}, \quad k=8.62 \times 10^{-5} \text{ eV/K}$$

Current Flow in Semiconductors

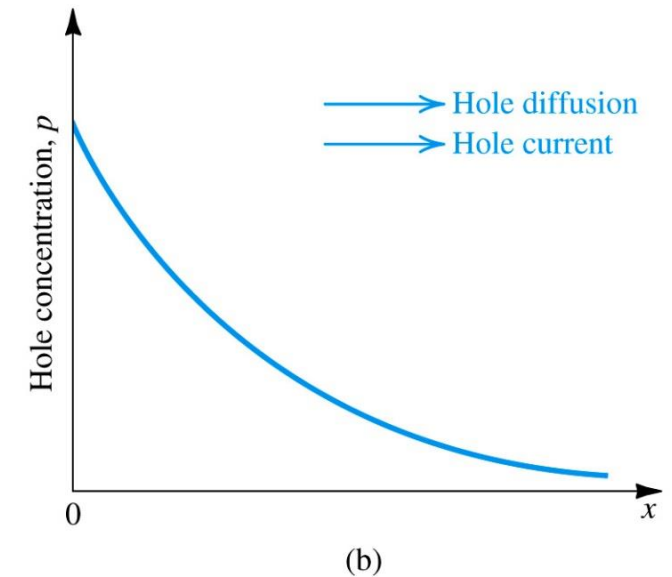
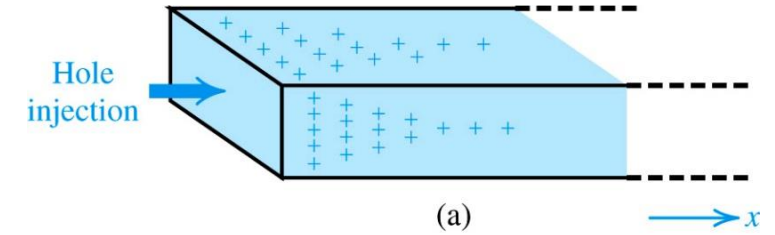
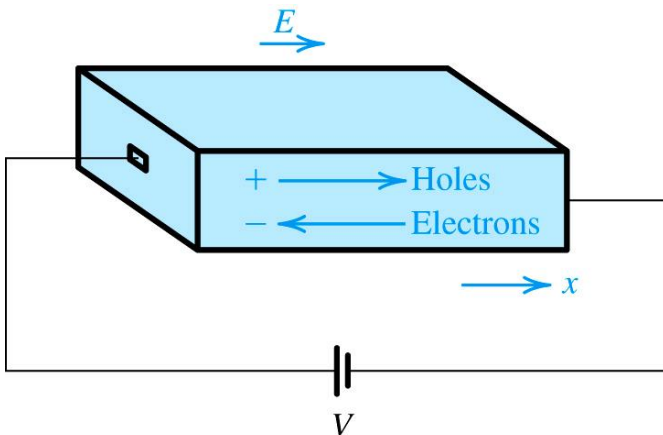
8/19/2019

... there are two distinctly different mechanisms for the movement of charge carriers and hence for current flow in semiconductors: *drift* and *diffusion*

Drift Current

When an electrical field E is established in a semiconductor crystal...

- Holes are accelerated in the direction of E !
- Free electrons are accelerated in the direction opposite of E !



Diffusion Current

When the density of charge carrier in a piece of semiconductor is not uniform...

- Charge carriers will diffuse from the region of high concentration to the region of low concentration!

Current Flow in Semiconductors

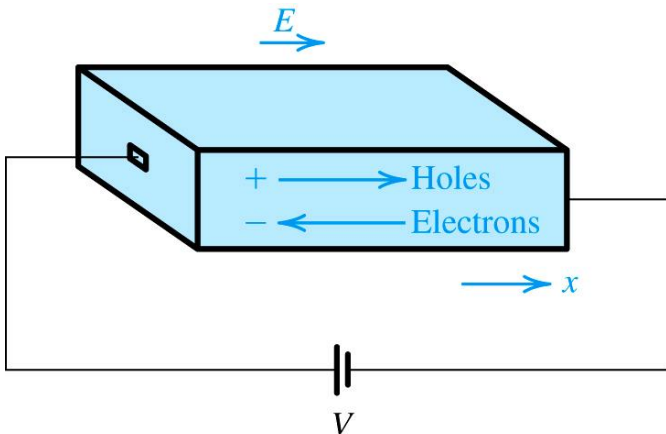
8/19/2019

... there are two distinctly different mechanisms for the movement of charge carriers and hence for current flow in semiconductors: *drift* and *diffusion*

Drift Current

$$J_{drift} = J_{p-drift} + J_{n-drift}$$

$$= q p \mu_p E + q n \mu_n E = q (p \mu_p + n \mu_n) E$$

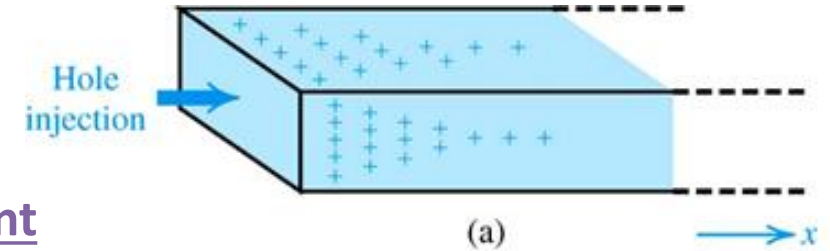


- J_x → current density [A/cm²]
- μ_p → hole mobility [cm²/V·s]
- μ_n → electron mobility [cm²/V·s]
- D_p → hole diffusion constant [cm²/s]
- D_n → electron diffusion constant [cm²/s]

Diffusion Current

$$J_{diff} = J_{p-diff} + J_{n-diff}$$

$$= -q D_p \frac{dp(x)}{dx} - q D_n \frac{dn(x)}{dx}$$



- Ohm's Law [A/cm²] $J = \sigma E$
- Conductivity [1/ Ω·cm] $\sigma = q (p \mu_p + n \mu_n)$
- Resistivity [Ω·cm] $\rho = \frac{1}{q (p \mu_p + n \mu_n)}$

Problem 3.6

8/19/2019

A young designer, aiming to develop intuition concerning conducting paths within an integrated circuit, examines the end-to-end resistance of a connecting bar 10 μm long, 3 μm wide, and 1 μm thick, made of various materials. The designer considers:

- intrinsic silicon
- n-doped silicon with $N_D=10^{16}/\text{cm}^3$
- n-doped silicon with $N_D=10^{18}/\text{cm}^3$
- p-doped silicon with $N_A=10^{16}/\text{cm}^3$
- Aluminum with resistivity of 2.8 $\mu\Omega\cdot\text{cm}$.

Find the resistance in each case. For intrinsic silicon use the data in Table 3.1. For doped silicon, assume $\mu_n=2.5\cdot\mu_p=1200\text{cm}^2/\text{V}\cdot\text{s}$. (Recall that $R=\rho L/A$)

- Silicon $n_i = 1.5 \times 10^{10} / \text{cm}^3$
- $q = 1.6 \times 10^{-19} \text{ C}$

	n (1/cm ³)	p (1/cm ³)	ρ $\Omega\cdot\text{cm}$	R Ω
a)	1.5×10^{10}	1.5×10^{10}	227×10^3	7.57M
b)	10^{16}	2.25×10^4	0.463	15
c)	10^{18}	2.25×10^2	4.63m	0.15
d)	2.25×10^4	10^{16}	0.768	25.6
e)	-	-	2.8 μ	93.3 μ